



Reactions of Difluorosilylene with Amines, Phosphines and Halomethanes The First Evidence of the Insertion of Difluorosilylene into Tetrafluorosilane

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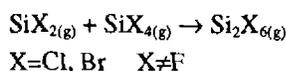
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The reactions of SiF₂/SiF₄ with amines, phosphines and various halomethanes were studied. The results show that in the presence of strong Lewis base (Et₃N, HNEt₂, PR₃, PR₂Cl), SiF₂ inserts initially into SiF₄ to form Si₂F₆, which was followed by subsequent reactions leading to products containing SiF₃ groups. This is the first report of the insertion of SiF₂ into SiF₄. When the reactants were a weaker base (such as R₂PCl₂, CX₃Br, X=F, Cl), insertion of SiF₂ into P-Cl and C-Br bonds became predominant.

INTRODUCTION

The chemistry of difluorosilylene has been extensively studied.¹ Like all other silylenes (SiX₂), the main chemistry of SiF₂ can be classified as (1) addition onto carbon-carbon double bonds and triple bonds,² and (2) insertion into M-H bonds, where M=O, S, and M-X bonds where M=B, and C, X=I.³

Unlike other members of the silylene family however, SiF₂ forms at -196 °C dimeric diradical species ·SiF₂SiF₂· (sometimes trimeric diradical), which is responsible for the majority of the chemistry of difluorosilylene in condensation experiments. Also, gaseous SiF₂ has long been known to be inert toward SiF₄ whereas other SiX₂ species insert into Si-X bonds of SiX₄ to form Si₂X₆ readily (X=Cl, Br).⁴

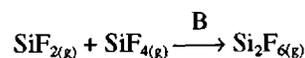


In a series of systematic studies we have clarified the dilemma of monomeric SiF₂ vs. dimeric ·SiF₂SiF₂· dispute.⁵ In this paper we report our rationalization about the other anomaly of SiF₂.

RESULTS AND DISCUSSION

(a) the insertion of SiF₂ into SiF₄

When the mixture of SiF₂ and SiF₄ passed the on-line IR cell, the spectrum showed typical bands for SiF₄ (1035 and 1029 cm⁻¹) and the broad bands near 860 cm⁻¹ for SiF₂.⁶ On introducing Lewis base (Et₃N, HNEt₂, PR₃, PR₂Cl) into the cell, the absorption of SiF₂ disappeared and the bands characteristic for Si₂F₆ (990, 822 cm⁻¹) grew up immediately (Fig. 1).



These results strongly suggest that in the presence of a Lewis base environment, SiF₂ inserts into Si-F bonds of SiF₄ to form Si₂F₆. In order to figure out the detailed function of the Lewis base, a number of organic phosphorus compounds were used as Lewis bases to measure the yield of Si₂F₆. The basicities and the cone angles of the phosphorus compounds and the yields of Si₂F₆ are listed in Table 1.

According to these results, we found that higher basicity causes higher yield of Si₂F₆. However, when phosphines of similar basicity such as PMe₃, PEt₃, PⁿPr₃, PⁱPr₃ are compared, it was found that a smaller cone angle causes a higher yield of Si₂F₆. When alkylchlorophosphines were used as Lewis bases, only monochlorophosphines showed the capability to help form Si₂F₆. In the cases of dichloro-

Table 1. The IR Absorption Intensity of Si₂F₆ Generated from the in situ Reaction of SiF₂/SiF₄ with Various Phosphines

Lewis base	I _{Si₂F₆}	cone angle, θ	pKa
PMe ₃	0.347	118	8.65
PMe ₂ Ph	0.279	122	6.50
PEt ₃	0.272	132	8.69
PEt ₂ H	0.277		
P(ⁿ Pr) ₃	0.243	132	-8.51
P(ⁱ Pr) ₃	0.200	160	-8.50
PMe ₂ Cl	0.212		
PMeCl ₂	Not observed		
PEt ₂ Cl	0.247		
PEtCl ₂	Not observed		
PCl ₃	Not observed		

I_{Si₂F₆} IR absorption intensity of Si₂F₆ observed at 990 cm⁻¹.

and trichloro-phosphines, where the basicity decreased as the chlorine atoms increased in the phosphines, no Si_2F_6 absorption could be observed in the IR spectra. It is generally known that the basicity and cone angle of a Lewis base are the indicators for the ability of coordination.⁷ Those results imply that the yield of Si_2F_6 is related to the coordinating ability of the base. The spectroscopic study and theoretical calculation of the 1:1 adduct of SiF_4 and NH_3 showed that $\text{SiF}_4 \cdot \text{NH}_3$ had a trigonal bipyramidal arrangement with NH_3 occupying one of the axial positions.⁸ The axial and equatorial Si-F bond distances were found to be 1.591 Å and 1.584 Å respectively, significantly longer than that in SiF_4 (1.556 Å).⁹

These data may suggest that the bonds of Si-F in the adduct are considerably weakened and the insertion of SiF_2 into Si-F bonds of the adduct may take place more easily.

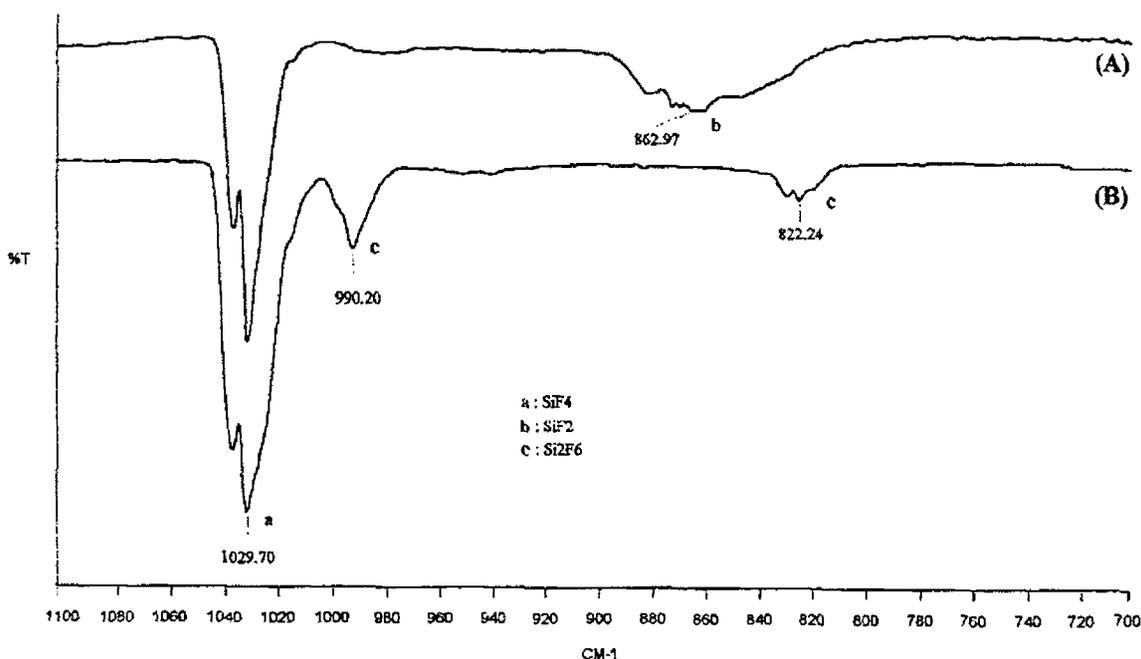
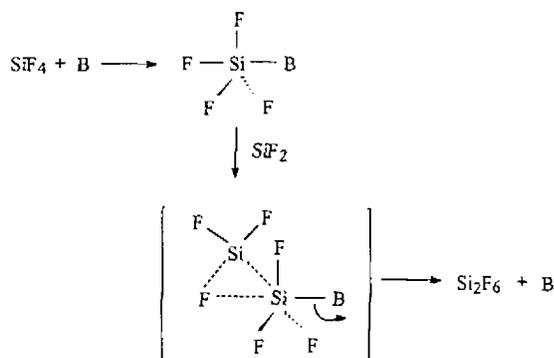


Fig. 1. The in situ IR experiment of $\text{SiF}_2/\text{SiF}_4$ and Et_3N : (A) before the introducing of Et_3N . (B) after the introducing of Et_3N .

(b) the insertion of SiF_2 into N-H bond

Ennan and Gavrilova reported the formation of adducts from SiF_4 and amines.¹⁰ In the case of diethylamine, thermal decomposition of the 1:2 adduct, $\text{SiF}_4 \cdot 2\text{Et}_2\text{H}$, yielded diethyltrifluorosilylamine Et_2NSiF_3 .¹¹ Since the difluorosilylene generated in our experimental conditions cannot be separated from the unreacted SiF_4 because it is actually a mixture of approximately 1:1 of $\text{SiF}_2:\text{SiF}_4$, the reactions between SiF_4 and the amines under these experimental conditions must be studied first as a "blank" test.

SiF_4 and NEt_3 were mixed in a 1:1 ratio and condensed at -190°C . On warming the condensate to room temperature, adduct products $\text{SiF}_4 \cdot \text{NEt}_3$ and $\text{SiF}_4 \cdot 2\text{NEt}_3$ were obtained. When the reaction was carried out with $\text{SiF}_4:\text{NEt}_3 = 1:2$, only the 1:2 adduct was obtained.

Under our experimental conditions, the reaction between SiF_4 and HNEt_2 yielded, in addition to $\text{SiF}_4 \cdot 2\text{NEt}_2\text{H}$ and Et_2NSiF_3 , a new product $(\text{Et}_2\text{N})_2\text{SiF}_2$. This compound was considered the product from double dehydrofluorination of $\text{SiF}_4 \cdot 2\text{NEt}_2\text{H}$.

In the cocondensation reaction between $\text{SiF}_2/\text{SiF}_4$ and NEt_3 the only products were $\text{SiF}_4 \cdot n\text{NEt}_3$ ($n = 1, 2$) and the $(\text{SiF}_2)_x$ polymer. However, an on-line IR experiment showed that the initial reaction product was hexafluorodisilane.

The cocondensation reaction between $\text{SiF}_2/\text{SiF}_4$ and diethylamine yielded Et_2NSiF_3 1, HSiF_3 2 and $\text{Et}_2\text{NSiF}_2\text{H}$ 3 in addition to the adduct product $\text{SiF}_4 \cdot 2\text{NEt}_2\text{H}$. This reac-

SiF₄ and Et₂NH in approximate 1:1 ratio were introduced into the vacuum system and condensed at -196 °C. After unreacted reagents were pumped out, a white solid and a colorless liquid were obtained. The white solid is SiF₄·2Et₂NH and the colorless liquid is compound **4**. The total yield of compound **4** and SiF₄·2Et₂NH base on the quantity of amine used was about 95%.

Reactions between SiF₂/SiF₄ and Amine

The reaction between SiF₂/SiF₄ and diethylamine was carried out at condensation reaction condition with different SiF₂/SiF₄: amine ratio. SiF₂/SiF₄ and diethylamine were mixed in different ratios and introduced into the vacuum system and condensed at -196 °C. Compounds **1**, **2** and **3** were obtained when the SiF₂/SiF₄: amine ratio was kept at approximately 1:1. When the SiF₂/SiF₄: amine ratio was kept to 0.5, **4**, **5** and SiF₄·2Et₂NH were obtained instead.

The reaction between SiF₂/SiF₄ and triethylamine was carried out at condensation reaction conditions. SiF₂/SiF₄ and Et₃N in approximate 1:1 ratio were introduced into the vacuum system and condensed at -196 °C. After unreacted reagents were pumped out, in addition to SiF₄·2NEt₃ (white) and SiF₄·NEt₃ (yellow), (SiF₂)_n polymer was obtained. No volatile product was found.

Reactions between Si₂F₆ and Diethylamine

Si₂F₆ and Et₂NH in approximate 1:1 ratio were introduced into the vacuum system and condensed at -196 °C. After unreacted reagents were pumped out, compounds **1**, **2**, **3**, **4** and **5** were obtained as colorless liquids. The total yield of those compounds based on the quantity of amine used was about 95%.

Reactions between Et₂NSiF₃ **1**, Et₂NSiF₂H **3** and Diethylamine

Compounds (Et₂N)₂SiF₂ **4** and (Et₂N)₂SiFH **5** were obtained by reacting Et₂NSiF₃ **1**, Et₂NSiF₂H **3** and Et₂NH at room temperature for 24 hr. The reaction was quantitative.

Reactions between SiF₂/SiF₄ and Various Halomethanes

The reaction between SiF₂/SiF₄ and various halomethanes was carried out at condensation reaction conditions with SiF₂/SiF₄ and halomethane in approximate 1:1 ratio. SiF₂/SiF₄ and halomethane were mixed and introduced into the vacuum system and condensed at -196 °C. After unreacted reagents were pumped out, in addition to (SiF₂)_n polymer insertion product **6** was obtained in the reaction of SiF₂/SiF₄ with bromotrichloromethane. In the reaction of SiF₂/SiF₄ with dibromodichloromethane insertion product **7** was obtained. The reaction of SiF₂/SiF₄ with dibromochloro-

rofluoromethane yielded insertion product **8**.

Reaction between SiF₂/SiF₄ and Dimethylchlorophosphine

The reaction between SiF₂/SiF₄ and dimethylchlorophosphine was carried out at condensation experiment conditions with SiF₂/SiF₄ and dimethylchlorophosphine in approximate 1:1 ratio. SiF₂/SiF₄ and dimethylchlorophosphine were mixed in the vacuum system and condensed at -196 °C. After unreacted reagents were removed, compounds **9**, **10**, **11** and various chlorofluorosilanes (SiCl₄, SiCl₃F, SiCl₂F₂, SiClF₃) were obtained in addition to (SiF₂)_n polymer.

Reaction between SiF₂/SiF₄ and Ethyldichlorophosphine

The reaction between SiF₂/SiF₄ and ethyldichlorophosphine was carried out at condensation experiment conditions with SiF₂/SiF₄ and ethyldichlorophosphine in approximate 1:1 ratio. The liquid collected at -30 °C containing compounds **13**, **14**, **15**, **16**, **17**, **18**, **20**, **21**, **22** and various chlorofluorosilanes (SiCl₄, SiCl₃F, SiCl₂F₂, SiClF₃) was obtained. A solid product (EtP)₅ **12** was also obtained.

The in situ IR Experiment

The gaseous reagents were mixed and introduced into the IR gas cell that was connected to the pumping system. The IR spectra were taken as soon as the reagents were mixed. The reactions were initiated by the insertion of SiF₂ into SiF₄ in the presence of Lewis bases such as Et₂NH, CH₃OH, trialkylphosphine, dialkylchlorophosphine, alkylidichlorophosphine. In these reactions, Si₂F₆ was the common initial product. In the in situ IR experiment of Si₂F₆ and Et₂NH compounds Et₂NSiF₃ **1**, HSiF₃ **2** and SiF₄ were detected.

The spectral data of the products:

(i) Compound **1** (C₂H₅)₂NSiF₃. Mass spectrum: m/e 157 (M⁺, C₄H₁₀F₃NSi⁺), 142 (C₃H₇F₃NSi⁺), 114 (CH₃F₃NSi⁺), 95 (CH₃F₂NSi⁺), 85 (F₃Si⁺). IR adsorption: 2978.5, 2943.0, 2884.3, 1389.9, 1223.1, 1174.2, 1107.6, 1053.3, 979.1, 953.9, 853.8, 789.5, 656.7, 502.6 cm⁻¹. ¹H NMR: δ 1.77 t, -NCH₂CH₃, 3.61 qq, -NCH₂CH₃. ¹⁹F NMR: δ -151 s (br), -NSiF₃. ¹³C NMR: δ 16.01 q, -NCH₂CH₃; 39.90 t, -NCH₂CH₃. ²⁹Si{¹H} NMR: δ -87.10 q, -NSiF₃. ¹J_{Si-F} = 204 Hz.

(ii) Compound **3** (C₂H₅)₂NSiF₂H. Mass spectrum: m/e 139 (M⁺, C₄H₁₁F₂NSi⁺), 138 (C₄H₁₀F₂NSi⁺), 124 (C₃H₈F₂NSi⁺), 110 (C₂H₆F₂NSi⁺). IR adsorption: 2250, 2166, 1107, 906, 793, 717 cm⁻¹. ¹H NMR: δ 1.7 t, -NCH₂CH₃; 3.6 qt, -NCH₂CH₃; 5.1 t, -SiF₂H. ¹⁹F NMR: δ -130.8 s (dq²), -SiF₂H. ¹³C NMR: δ 16.3 t (qm), -NCH₂CH₃; 39.9 t (tm),

-NCH₂CH₃. ²⁹Si{¹H} NMR: δ -53.49 s, -SiF₂H. ¹J_{Si-F} = 274 Hz.

(iii) Compound 4 [(C₂H₅)₂NSiF₂]. Mass spectrum: m/e 210 (M⁺, C₈H₂₀F₂N₂Si⁺), 181 (C₆H₁₅F₂N₂Si⁺), 136 (C₄H₈F₂NSi⁺), 122 (C₃H₆F₂NSi⁺), 86 (C₃H₈NSi⁺). ¹H NMR: δ 1.75 t, -NCH₂CH₃; 3.58 qt, -NCH₂CH₃. ¹⁹F NMR: δ -144.0 s (br), -NSiF₂N-. ¹³C NMR: δ 16.24 q (qt), -NCH₂CH₃; 40.88 t (qtd), -NCH₂CH₃. ²⁹Si{¹H} NMR: δ -64.4 t, -NSiF₂N-. ¹J_{Si-F} = 222 Hz.

(iv) Compound 5 [(C₂H₅)₂NSiFH]. ¹H NMR: δ 1.8 t, -NCH₂CH₃; 3.6 qd, -NCH₂CH₃; 5.1 d, -SiFH-. ¹⁹F NMR: δ -138.6 s (dm), -SiFH-. ¹J_{Si-F} = 273 Hz.

(v) Compound 6 CCl₃SiF₂Br. Mass spectrum: m/e 227 (M-Cl⁺, CCl₂BrF₂Si⁺), 183 (M-Br⁺, CCl₃F₂Si⁺), 145 (BrF₂Si⁺), 82 (CCl₂⁺), 47 (CCl₂⁺, FSi⁺). ¹⁹F NMR: δ -124.3 s (s), -SiF₂Br. ¹³C NMR: δ 83.5 t (t), -CCl₃. ¹J_{Si-F} = 320.0 Hz, ²J_{C-F} = 25.2 Hz.

(vi) Compound 7 CCl₂BrSiF₂Br. Mass spectrum: m/e 271 (M-Cl⁺, CClBrF₂Si⁺), 227 (M-Br⁺, CCl₂BrF₂Si⁺), 192 (M-ClBr⁺, CClBrF₂Si⁺), 145 (BrF₂Si⁺), 47 (CCl₂⁺, FSi⁺). ¹⁹F NMR: δ -124.0 s (s), -SiF₂Br. ¹³C NMR: δ 64.5 t (t), -CBrCl₂. ¹J_{Si-F} = 320.1 Hz, ²J_{C-F} = 24.1 Hz.

(vii) Compound 8 CClBrFSiF₂Br. Mass spectrum: m/e 255 (M-Cl⁺, CBrF₃Si⁺), 211 (M-Br⁺, CClBrF₃Si⁺), 178 (M-ClBr⁺, CBrF₃Si⁺), 132 (ClF₃Si⁺), 47 (CCl₂⁺, FSi⁺). ¹⁹F NMR: δ -80.05 br (br), CBrF₃Cl, δ -124.5 AB (AB), -SiF₂Br. ¹³C NMR: δ 99.7 dt (dt), -CClBrF. ¹J_{Si-F} = 323.6 Hz, ²J_{Si-F} = 49.6 Hz, ²J_{C-F} = 28.0 Hz, ¹J_{C-F} = 301.0 Hz, ²J_{F-F} = 55.3 Hz, ³J_{F-F} = 0.8 Hz.

(viii) Compound 9 [(CH₃)₂P]₂. Mass spectrum: m/e 122 (M⁺, C₄H₁₂P₂⁺), 107 (C₃H₉P₂⁺), 79 (CH₅P₂⁺), 61 (CH₂P⁺), 45 (CH₂P⁺). ¹H NMR: δ 1.11 A₆XX'A₆, -P(CH₃)₂. ¹³C NMR: δ 10.68 t (qt). -P(CH₃)₂ ¹J_{C-H} = 128.9 Hz. ³¹P{¹H} NMR: δ -58.2 s(m). -P(CH₃)₂ ¹J_{C-P} = ²J_{C-P} = 3.9 Hz, ²J_{H-P} = 2.9 Hz, ³J_{H-P} = 11.25 Hz.

(ix) Compound 10 (CH₃)₂PSiCl₃. Mass spectrum: m/e 194 (M⁺, C₂H₆Cl₃PSi⁺), 133 (SiCl₃⁺), 113 (CH₃SiCl₂⁺), 96 (C₂H₅PCl₃⁺), 61 (C₂H₆P⁺). ¹H NMR: δ 1.06 d, -P(CH₃)₂. ¹³C NMR: δ 8.38 d (qdq). -P(CH₃)₂. ³¹P{¹H} NMR: δ -96.5 s(m). -P(CH₃)₂. ²⁹Si{¹H} NMR: δ -64.4 t, -PSiCl₃. ¹J_{C-P} = 18.1 Hz, ¹J_{Si-P} = 82.5 Hz, ²J_{H-P} = 3.9 Hz.

(x) Compound 11 [(CH₃)₂P]₂SiCl₂. Mass spectrum: m/e 220 (M⁺, C₄H₁₂Cl₂P₂Si⁺), 205 (C₃H₉Cl₂P₂Si⁺), 160 (C₂H₇Cl₂PSi⁺), 113 (CH₃Cl₂Si⁺), 61 (C₂H₆P⁺). ¹H NMR: δ 1.23 A₆XX'A₆, -P(CH₃)₂. ¹³C NMR: δ 7.0 AXX' (m). -P(CH₃)₂ ¹J_{C-H} = 128.9 Hz. ³¹P{¹H} NMR: δ -109.5 s(m). -P(CH₃)₂ ²⁹Si{¹H} NMR: δ 45.3 t, -PSiCl₂. ¹J_{Si-P} = 88.1 Hz, ²J_{H-P} = 3.1 Hz.

(xi) Compound 13 C₂H₅P(SiF₃)₂. Mass spectrum: m/e 230 (M⁺, C₂H₅F₆PSi₂⁺), 202 (HF₆PSi₂⁺), 183 (HF₅PSi₂⁺), 85

(SiF₃⁺), 57 (C₄H₉⁺). ¹H NMR: δ 1.01 qm, -PCH₂CH₃, 1.61 tm, -PCH₂CH₃. ¹³C NMR: δ 5.93 d, -PCH₂CH₃, 16.14 d, -PCH₂CH₃. ³¹P{¹H} NMR: δ -220.3 m(m). -PCH₂CH₃. ¹⁹F{¹H} NMR: δ -117.45, d, -PSiF₃. ¹J_{Si-F} = 328.1 Hz, ²J_{F-F} = 10.77 Hz, ¹J_{C-P} = 12.5 Hz, ²J_{C-P} = 9.2 Hz.

(xii) Compound 14 C₂H₅P(SiF₃)(SiClF₂). Mass spectrum: m/e 246 (M⁺, C₂H₅ClF₅PSi₂⁺), 218 (HClF₅PSi₂⁺), 183 (HF₅PSi₂⁺), 85 (SiF₃⁺), 57 (C₄H₉⁺). ¹H NMR: δ 1.06 qm, -PCH₂CH₃, 1.63 tm, -PCH₂CH₃. ¹³C NMR: δ 7.21 d, -PCH₂CH₃, 16.01 d, -PCH₂CH₃. ³¹P{¹H} NMR: δ -196.9 qt (qum). -PCH₂CH₃. ¹⁹F{¹H} NMR: δ -117.66, dt, -PSiF₃, -104.3, AB, -PSiF₂Cl. ¹J_{Si-F} = 328.6 Hz, ²J_{F-F} = 58.0 Hz, ¹J_{C-P} = 13.1 Hz, ²J_{C-P} = 10.3 Hz, ²J_{F-P} = 9.87 Hz, ³J_{H-H} = 7.65 Hz.

(xiii) Compound 15 C₂H₅P(SiF₃)(SiFCl₂). Mass spectrum: m/e 262 (M⁺, C₂H₅Cl₂F₄PSi₂⁺), 234 (HCl₂F₄PSi₂⁺), 215 (HF₃PSi₂⁺), 199 (HClF₄PSi₂⁺), 117 (SiFCl₂⁺). ¹H NMR: δ 1.12 qm, -PCH₂CH₃, 1.74 tm, -PCH₂CH₃. ¹³C NMR: δ 8.52 d, -PCH₂CH₃, 15.68 d, -PCH₂CH₃. ³¹P{¹H} NMR: δ -175.1 dq (dqum). -PCH₂CH₃. ¹⁹F{¹H} NMR: δ -117.87, dd, -PSiF₃, -95.5, dq, -PSiFCl₂. ¹J_{Si-F} = 329.7 Hz, ¹J_{Si-F} = 375.5 Hz, ⁴J_{F-P} = 2.90 Hz, ¹J_{C-P} = 13.9 Hz, ²J_{C-P} = 11.3 Hz, ²J_{F-P} = 8.98 Hz, ³J_{H-H} = 7.71 Hz.

(xiv) Compound 16 C₂H₅P(SiF₃)(SiCl₃). Mass spectrum: m/e 278 (M⁺, C₂H₅Cl₃F₃PSi₂⁺), 250 (HCl₃F₃PSi₂⁺), 215 (HCl₂F₃PSi₂⁺), 133 (Cl₃Si⁺), 98 (SiCl₂⁺). ¹H NMR: δ 1.18 qm, -PCH₂CH₃, 1.72 tm, -PCH₂CH₃. ¹³C NMR: δ 9.71 d, -PCH₂CH₃, 15.30 d, -PCH₂CH₃. ³¹P{¹H} NMR: δ -155.9 q (qm). -PCH₂CH₃. ¹⁹F{¹H} NMR: δ -118.22, d, -PSiF₃. ¹J_{Si-F} = 330.8 Hz, ¹J_{Si-P} = 57.5 Hz, ¹J_{C-P} = 14.3 Hz, ²J_{C-P} = 12.6 Hz, ²J_{F-P} = 8.53 Hz, ³J_{H-H} = 7.67 Hz.

(xv) Compound 17 C₂H₅P(SiClF₂)₂. Mass spectrum: m/e 262 (M⁺, C₂H₅Cl₂F₄PSi₂⁺), 234 (HCl₂F₄PSi₂⁺), 215 (HF₃PSi₂⁺), 199 (HClF₄PSi₂⁺), 117 (SiFCl₂⁺). ¹H NMR: δ 1.12 qm, -PCH₂CH₃, 1.65 tm, -PCH₂CH₃. ¹³C NMR: δ 8.52 d, -PCH₂CH₃, 15.68 d, -PCH₂CH₃. ³¹P{¹H} NMR: δ -175.1 m (m). -PCH₂CH₃. ¹⁹F{¹H} NMR: δ -104.5, AB, -PSiF₂Cl. ²J_{F-F} = 59.0 Hz, ¹J_{C-P} = 13.5 Hz, ²J_{C-P} = 11.3 Hz, ²J_{F-P} = 7.8 Hz, ²J_{F-P} = 2.8 Hz, ³J_{H-H} = 7.71 Hz.

(xvi) Compound 18 C₂H₅P(SiFCl₂)(SiClF₂). Mass spectrum: m/e 278 (M⁺, C₂H₅Cl₃F₃PSi₂⁺), 250 (HCl₃F₃PSi₂⁺), 215 (HCl₂F₃PSi₂⁺), 133 (Cl₃Si⁺), 98 (SiCl₂⁺). ¹H NMR: δ 1.18 qm, -PCH₂CH₃, 1.72 tm, -PCH₂CH₃. ¹³C NMR: δ 9.73 d, -PCH₂CH₃, 15.18 d, -PCH₂CH₃. ³¹P{¹H} NMR: δ -155.1 ddd (dddum). -PCH₂CH₃. ¹⁹F{¹H} NMR: δ -95.8, dt, -PSiFCl₂, -104.0, AB, -PSiF₂Cl. ¹J_{Si-F} = 376.6 Hz, ¹J_{C-P} = 14.3 Hz, ²J_{C-P} = 12.9 Hz, ²J_{F-P} = 7.9 Hz, ²J_{F-P} = 13 Hz, ²J_{F-P} = 3.7 Hz, ³J_{H-H} = 7.67 Hz.

(xvii) Compound 19 C₂H₅P(SiCl₃)(SiClF₂). Mass spectrum: m/e 294 (M⁺, C₂H₅Cl₄F₂PSi₂⁺), 266 (HCl₄F₂PSi₂⁺), 231 (HCl₃F₂PSi₂⁺), 142 (C₂H₅PSiFCl⁺), 114 (HPSiFCl⁺). ¹H

NMR: δ 1.22 qm, $-PCH_2CH_3$, 1.79 tm, $-PCH_2CH_3$. ^{13}C NMR: δ 10.82 d, $-PCH_2CH_3$, 14.85 d, $-PCH_2CH_3$. $^{31}P\{^1H\}$ NMR: δ -137.4 dd (m). $-PCH_2CH_3$. $^{19}F\{^1H\}$ NMR: δ -104.0, AB, $-PSiF_2Cl$. $^1J_{Si-P} = 45.3$ Hz, $^1J_{C-P} = 15.1$ Hz, $^2J_{C-P} = 13.9$ Hz, $^2J_{P-P} = 9.7$ Hz, $^2J_{F-P} = 4.7$ Hz, $^3J_{H-H} = 7.65$ Hz, $^2J_{F-F} = 57$ Hz.

(xviii) Compound **20** $C_2H_5P(SiFCl_2)_2$. Mass spectrum: m/e 294 (M^+ , $C_2H_5Cl_4F_2PSi_2^+$), 266 ($HCl_4F_2PSi_2^+$), 231 ($HCl_3F_2PSi_2^+$), 142 ($C_2H_5PSiFCl^+$), 114 ($HPSiFCl^+$). 1H NMR: δ 1.22 qm, $-PCH_2CH_3$, 1.79 tm, $-PCH_2CH_3$. ^{13}C NMR: δ 10.85 d, $-PCH_2CH_3$, 14.80 d, $-PCH_2CH_3$. $^{31}P\{^1H\}$ NMR: δ -136.8 dd (m). $-PCH_2CH_3$. $^{19}F\{^1H\}$ NMR: δ -96.1, d (dm), $-PSiFCl_2$. $^1J_{Si-F} = 378.2$ Hz, $^1J_{Si-P} = 44.5$ Hz, $^1J_{C-P} = 15.1$ Hz, $^2J_{C-P} = 13.8$ Hz, $^2J_{F-P} = 12.1$ Hz, $^2J_{F-P} = 4.7$ Hz, $^3J_{H-H} = 7.65$ Hz.

(xix) Compound **21** $C_2H_5P(SiCl_3)(SiFCl_2)$. Mass spectrum: m/e 310 (M^+ , $C_2H_5Cl_3FPSi_2^+$), 295 ($CH_2Cl_3FPSi_2^+$), 231 ($HCl_3FPSi_2^+$), 142 ($C_2H_5PSiFCl^+$), 114 ($HPSiFCl^+$). 1H NMR: δ 1.28 qm, $-PCH_2CH_3$, 1.84 tm, $-PCH_2CH_3$. ^{13}C NMR: δ 11.9 d, $-PCH_2CH_3$, 14.60 d, $-PCH_2CH_3$. $^{31}P\{^1H\}$ NMR: δ -121.1 d (dm). $-PCH_2CH_3$. $^{19}F\{^1H\}$ NMR: δ -96.5, d(dm), $-PSiFCl_2$. $^1J_{Si-F} = 379.3$ Hz, $^1J_{C-P} = 15.9$ Hz, $^2J_{C-P} = 14.8$ Hz, $^2J_{F-P} = 11.7$ Hz, $^3J_{H-H} = 7.72$ Hz.

(xx) Compound **22** $C_2H_5P(SiCl_3)_2$. Mass spectrum: m/e 326 (M^+ , $C_2H_5Cl_6PSi_2^+$), 298 ($HCl_6PSi_2^+$), 263 ($HCl_5PSi_2^+$), 130 (HCl_2PSi^+), 63 ($SiCl^+$). 1H NMR: δ 1.33 qm, $-PCH_2CH_3$, 1.89 tm, $-PCH_2CH_3$. ^{13}C NMR: δ 12.96 d, $-PCH_2CH_3$, 14.41 d, $-PCH_2CH_3$. $^{31}P\{^1H\}$ NMR: δ -106.4 s (m). $-PCH_2CH_3$. $^{19}F\{^1H\}$ NMR: δ -96.5, d(dm), $-PSiFCl_2$. $^1J_{Si-P} = 66.3$ Hz, $^1J_{C-P} = 16.8$ Hz, $^2J_{C-P} = 15.6$ Hz, $^3J_{H-H} = 7.9$ Hz.

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Key Words

Difluorosilylene; Amine; Phospine; Insertion.

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